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Sheet 1 Atty. Docket No. Serial No. Form PTO-1449 **U.S. Department of Commerce** (Rev. 2-32) Patent & Trademark Office A-20929 Not yet assigned Applicant INFORMATION DISCLOSURE STATEMENT Alek C. CHEN (Use several sheets if necessary) Filing Date Group Concurrently Herewith Not yet assigned **U.S. PATENT DOCUMENTS** Examiner **Document Number** Date Name Class Sub-Filing Date Initial (if appropriate) Class 5,327,221 07-1994 SAITOH et al 5,373,232 12-1994 CRESSWELL et al 5,585,211 12-1996 FIRSTEIN et al 5,656,403 08-1997 SHIEH FOREIGN PATENT DOCUMENTS Translation Sub-Document Date Country Class class Yes/No OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Scott HECTOR et al. "X-Ray Lithography for ≤100 nm Ground Rules In Complex Patterns," J. Vac. Society Technol. B, Vol 15, No 6, Nov/Dec. 1997, pp. 2517-2521 **EXAMINER** DATE CONSIDERED 2/6/03 Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and EXAMINER:

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